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SP03-018

UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: COUILLARD, JAMES G., et al
Serial No: 10/779582
Filed: 2/12/2004
For: GLASS-BASED SOI STRUCTURES

Examiner: Unknown
Group Art Unit: Unknown

INFORMATION DISCLOSURE STATEMENT
UNDER 37 C.F.R. §§ 1.56, 1.97 – 1.98

Commissioner of Patents
Alexandria, VA 22313-1450

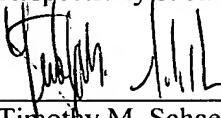
Dear Sir:

The Examiner's attention is hereby directed to the following reference(s) listed on the attached Form PTO-1449 for consideration in connection with the examination of the above-identified patent application. One copy of the reference(s) is enclosed.

This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that each or all of the enclosed documents constitute "prior art." If it should be determined that any of the submitted documents do not constitute "prior art" under United States law, applicant(s) reserve the right to present to the office the relevant facts and law regarding the appropriate status of such documents.

Applicant(s) further reserve the right to take appropriate action to establish the patentability of the disclosed invention over the enclosed references, should one or more of the references be applied against the claims of the present application.

Respectfully submitted,

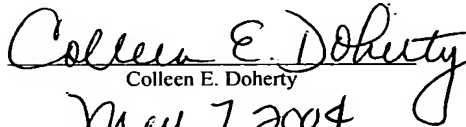


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I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to Commissioner of Patents, Alexandria, Va, 22313-1450 on

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Colleen E. Doherty
May 7 2004
Date of Signature



FORM PTO-1449 (MODIFIED) LIST OF PATENTS AND PUBLICATIONS FOR APPLICANTS INFORMATION DISCLOSURE STATEMENT	ATTORNEY DOCKET NO.	SERIAL NO.
	SP03-018	10/779582
	APPLICANT MACH J, et al.	
	FILING DATE 2/12/2004	GROUP: Unknown

REFERENCE DESIGNATION				U.S. PATENT DOCUMENTS			
Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date if Approp.
	AA	4,294,602	10/13/81	Horne	65	40	
	AB	5,374,564	12/20/94	Bruel	437	24	
	AC	5,442,205	8/15/95	Brasen et al	257	191	
	AD	5,559,043	9/24/96	Bruel	437	24	
	AE	5,909,627	6/1/99	Egloff	438	406	
	AF	6,048,411	4/11/00	Henley et al	148	33.5	
	AG	6,107,653	8/22/00	Fitzgerald	257	191	
	AH	6,140,209	10/31/00	Iwane et al	438	458	
	AI	6,150,239	11/21/00	Goesele et al	438	458	
	AJ	6,211,041	4/3/01	Ogura	438	458	
	AK	6,251,754	6/26/01	Ohshima et al	438	506	
	AL	6,309,950	10/30/01	Forbes	438	455	
	AM	6,319,867	11/20/01	Chacon et al	501	66	
	AR	6,323,108	11/27/01	Kub et al	438	458	
	AS	6,335,231	1/1/02	Yamazaki et al	438	151	
	AT	6,391,740	5/21/02	Cheung et al	438	455	
	AU	6,573,126	6/3/03	Cheng et al	438	149	
	AV	6,593,641	7/15/03	Fitzgerald	257	616	

FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Sub-Class	Translation Yes No
	AW	EP0557588	9/1/93	Europe	93	35	X
	AX	EP0539741	5/5/93	Europe	93	18	X

OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)	
AY	M. Bruel; "Silicon on insulator material technology"; Electronics Letters; July 1995; Vol. 13, No. 14; pages 1201-1202
AZ	Cioccio et al.; "Silicon carbide on insulator formation using the Smart Cut process"; Electronics Letters; June 1996; Vol. 32, No. 12; pages 1144-1145
BA	Marshall et al; "Measurement of adherence of residually stressed thin films by indentation. I. Mechanics of interface delamination"; J. Appl. Phys; November 1984; Vol. 56, No. 10; pages 2632-2638
BB	Bister et al; "Ranges of the 0.3-2 MeV H ⁺ and 0.7-2 MeV H ₂ ⁺ ions in Si and Ge"; Radiation Effects; 1982; Vol. 59; pages 199-202.

	BC	Lee, et al.: "Semiconductor layer transfer by anodic wafer bonding"; IEEE International SOI Conference; October 1997; Pages 40-41
	BD	Spangler, et al.; "A technology for high-performance single-crystal silicon-on-insulator transistors"; IEEE Electron Device Letters; Vol. 8, No. 4; April 1987; pages 137-139

EXAMINER:

DATE CONSIDERED:

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609: draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.